

Sub
C2
B2
3. (Twice amended) A liquid crystal display device comprising a switching element formed on a substrate, a pixel electrode connected to said switching element, and a reflection layer,

wherein said pixel electrode is formed of a transparent conductive film, and
wherein said reflection layer formed of a dielectric multi-layer film is provided under said pixel electrode, and

wherein said pixel electrode has a thickness of 50.5 nm to 88.4 nm, and said thickness is satisfied with $\lambda/4$.

Sub
C3
B3
5. (Twice amended) A liquid crystal display device comprising a switching element formed on a substrate, a pixel electrode connected to said switching element, and a reflection layer,

wherein said switching element is connected to a capacitance,
wherein said capacitance comprising a common electrode formed of a transparent conductive film, a dielectric film formed on said common electrode, and said pixel electrode formed of a transparent conductive film formed on said dielectric film,

wherein said reflection layer formed of a dielectric multi-layer film is provided below said common electrode, and

wherein said pixel electrode has a thickness of 50.5 nm to 88.4 nm, and said thickness is satisfied with $\lambda/4$.

Sub
C4
B4
8. (Twice amended) A method of manufacturing a liquid crystal display device, comprising the steps of:
forming a switching element formed on a substrate;
a reflection layer formed of a dielectric multi-layer film above said switching element; and,
forming a pixel electrode formed of a transparent conductive film on said reflection layer,